

0385 U.S. PTO  
10/027882  
12/21/01

PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10027882	12/21/2001	385		2874	<i>Abm. J.</i>

\*\*APPLICANTS: Novotny Vlad;

\*\*CONTINUING DATA VERIFIED:

THIS APPLN CLAIMS BENEFIT OF 60/206,744 05/24/2000

\*\* FOREIGN APPLICATIONS VERIFIED:

PG-PUB DO NOT PUBLISH ☒

RESCIND ☐

Foreign priority claimed ☐ yes ☐ no  
35 USC 119 conditions met ☐ yes ☐ no

Verified and Acknowledged Examiners's initials

ATTORNEY DOCKET NO

A0-001-2D

TITLE : Deep-well lithography process for forming micro-electro-mechanical structures

U.S. DEPT. OF COMM./PAT. & TM-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED

Assistant Examiner

CLAIMS ALLOWED

Total Claims

Print Claim for  
O.G

ISSUE FEE

Amount Due

Date Paid

DRAWING

Sheets Drwg.

Figs. Drwg.

Print Fig.

Primary Examiner

PREPARED FOR ISSUE

Application Examiner



TERMINAL

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☐ CD-ROM

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